

## CLAIMS

1. A manufacturing method of a semiconductor device comprising:  
forming a plurality of circuit portions each having a modulation circuit, a  
5 demodulation circuit, and a logic circuit over an insulating substrate by a first exposure means; and  
forming a plurality of different memory circuits over the substrate by a second exposure means.
- 10 2. A manufacturing method of a semiconductor device comprising:  
forming an object to be processed over an insulating substrate;  
applying a photoresist on the object;  
exposing the photoresist by a first exposure means;  
exposing the photoresist by a second exposure means;  
15 developing the photoresist exposed by the first exposure means and the second exposure means; and  
etching the object by using the developed photoresist to form a plurality of first patterns of circuit portions each having a modulation circuit, a demodulation circuit, and a logic circuit and a plurality of second patterns of different memory  
20 circuits.
3. A manufacturing method of a semiconductor device comprising:  
forming an object to be processed over an insulating substrate;  
applying a first photoresist on the object;  
25 exposing the first photoresist by a first exposure means;  
developing the exposed first photoresist;  
etching the object by using the developed first photoresist to form a plurality of first patterns of circuit portions each having a modulation circuit, a demodulation circuit, and a logic circuit;  
30 applying a second photoresist on the object;

exposing the second photoresist by a second exposure means;  
developing the exposed second photoresist; and  
etching the object by using the developed second photoresist to form a  
plurality of second patterns of different memory circuits.

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4. A manufacturing method of a semiconductor device comprising:  
forming an object to be processed over an insulating substrate;  
applying a photoresist on the object;  
exposing the photoresist by a first exposure means;  
10 exposing the photoresist by a second exposure means;  
developing the photoresist exposed by the first exposure means and the  
second exposure means; and  
etching the object by using the developed photoresist to form a plurality of  
first patterns of first circuit portions and a plurality of second patterns of different  
15 second circuit portions,  
wherein the second exposure means can change the contents of exposure  
depending on program.

5. A manufacturing method of a semiconductor device comprising:  
20 forming an object to be processed over an insulating substrate;  
applying a photoresist on the object;  
exposing the photoresist by a first exposure means;  
exposing the photoresist by a second exposure means;  
developing the photoresist exposed by the first exposure means and the  
25 second exposure means; and  
etching the object by using the developed photoresist to form a plurality of  
first patterns of first circuit portions and a plurality of second patterns of different  
second circuit portions,  
wherein different data is stored in each of the second circuit portions.

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6. The manufacturing method of a semiconductor device according to any one of claims 1 to 3, wherein the memory circuit is a mask ROM.

7. The manufacturing method of a semiconductor device according to claim  
5 4 or 5, wherein the second circuit portion is a mask ROM.

8. The manufacturing method of a semiconductor device according to any one of claims 1 to 3, wherein the difference among the plurality of memory circuits is data stored therein.  
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9. The manufacturing method of a semiconductor device according to claim 4, wherein the difference among the plurality of second circuit portions is data stored therein.

10. The manufacturing method of a semiconductor device according to any one of claims 1 to 3 and 5, wherein the second exposure means can change the contents of exposure depending on program.  
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11. The manufacturing method of a semiconductor device according to any one of claims 1 to 5, wherein the first exposure means is an exposure means using a mirror projection exposure system.  
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12. The manufacturing method of a semiconductor device according to any one of claims 1 to 5, wherein the first exposure means is an exposure means using a step and repeat exposure system.  
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13. The manufacturing method of a semiconductor device according to any one of claims 1 to 5, wherein the first exposure means is an exposure means using a step and scan exposure system.  
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14. The manufacturing method of a semiconductor device according to any one of claims 1 to 5, wherein the second exposure means is an exposure means using an electron beam exposure system.

5           15. The manufacturing method of a semiconductor device according to any one of claims 1 to 5, wherein the second exposure means is an exposure means using a laser exposure system.

10           16. The manufacturing method of a semiconductor device according to any one of claims 1 to 5, wherein a portion exposed by the second exposure means is a contact hole.

15           17. The manufacturing method of a semiconductor device according to any one of claims 1 to 5, wherein the insulating substrate is one selected from the group consisting of a glass substrate, a plastic substrate, and a film insulator.

20           18. An IC card, an IC tag, an RFID, a transponder, a bill, a security, a passport, an electronic apparatus, a bag, and a garment each comprising a semiconductor device manufactured by the manufacturing method according to any one of claims 1 to 5.

25           19. The manufacturing method of a semiconductor device according to claim 4 or 5, wherein each of the first circuit portions comprises a modulation circuit, a demodulation circuit, and a logic circuit.

20           20. The manufacturing method of a semiconductor device according to claim 4 or 5, wherein each of the second circuit portions comprises different memory circuits.